

IN THE CLAIMS

1 (Currently Amended). A photoresist comprising:
a photoacid generator that includes a cation with a base atom coupled to at least three entirely sigma-bonded non-cyclic moieties.

2 (Original). The photoresist of claim 1 including an anion and a cation, wherein said cation does not include phenyl.

Claims 3 and 4 (Canceled).

5 (Previously Presented). The photoresist of claim 1 wherein said photoacid generator is more transparent than phenyl containing photoacid generators.

Claims 6-12 (Canceled).

13 (Original). The photoresist of claim 10 wherein said base atom is sulfur.

14 (Currently Amended). A method comprising:
forming a photoresist with a photoacid generator with a cation having a base atom coupled to at least three entirely sigma-bonded non-cyclic moieties.

15 (Original). The method of claim 14 including providing a cation to said photoacid generator that does not include phenyl.

16 (Previously Presented). The method of claim 14 including providing an entirely sigma-bonded cation.

Claim 17 (Canceled).

18 (Previously Presented). The method of claim 14 including forming a photoresist with a photoacid generator that is more transparent than phenyl containing photoacid generators.

Claims 19-22 (Canceled).

23 (Currently Amended). A photoresist comprising:
a photoacid generator including a cation that is entirely sigma-bonded and including a base atom coupled to at least three non-cyclic moieties.

24 (Original). The photoresist of claim 23 wherein said cation includes a base atom coupled by sigma-bonds to at least three moieties.

25 (Original). The photoresist of claim 23 wherein said moieties are alkyl or substituted alkyls.

26 (Original). The photoresist of claim 25 wherein said alkyl or substituted alkyl includes a halogen, ether, ester, carbonate, or ketone.

27 (Original). The photoresist of claim 23 wherein said photoacid generator includes a sulfur atom sigma-bonded to alkyl groups.

28 (Original). The photoresist of claim 24 wherein said base atom is sulfur.